



MICROFOCUSING OF THE FERMI@ELETTRA FEL BEAM WITH A K-B ACTIVE OPTICS SYSTEM: SPOT SIZE PREDICTIONS

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FERMI@Elettra seeded FEL



FEL 1 from ~100 nm down to 20 nm - source distance (to spectrometer) 57.5 m Divergence $\sigma(\mu rad) = 1.25 \lambda(nm)$ - Source dimension = 60 μm (sigma)

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FEL 2 from 20 nm down to ~4 nm - source distance (to spectrometer) 49.8 m Divergence $\sigma(\mu rad) = 1.5 \lambda(nm)$ - Source dimension = 123 μm (sigma)



K-B active optic system - DiProl



End-stations need high flux - great demagnification K-B system advantages

Decoupling vertical and horizontal beam components

 Thick ellipsoidal mirrors with the great demagnification request are difficult to realize

K-B bendable system advantages

- Focalization of the 2 sources at different distance with the same couple of mirrors
- Difficult realization of thick elliptical mirror with this demanding demagnification
- Improvement of the FEL beam wave-front

Holder K-B mirrors





K-B active optic system - DiProl

Profile surface characterization with Long Trace Profilometer

- LTP profile measurements 1mm step
- Best possible profile reached through the <u>Adaptive Correction Tool</u> software
- Measurements with Zygo interferometer and AFM rms under specifications (<3A spatial range 2µm - 0.5mm)
- Proof of the system stability



K-B Vertical mirror - residual surface profile K-B Horizontal mirror - residual surface profile

K-B active optic system - DiProl

Ray tracing simulations with Shadow code

K-B vertical mirror at best focus (+2mm to the nominal focus)

FWHM_{ray-tracing} = 18 µm

K-B horizontal mirror at best focus (-2mm to the nominal focus)

FWHM_{ray-tracing} = 10.5 µm



Focal spot measurements - DiProl Phosphorus screen and PMMA ablation

First phase

- rough angle alignment
- optimized mirror bending
- best spot achieved on Phosphorus screen FWHM_{32nm}=60x70 µm

Second phase

refine angle alignment

15 um

- optimized mirror bending
 - best spot achieved on Phosphorus screen FWHM_{32nm}=40x42 μm seen with PMMA ablation FWHM_{32nm}=15x26 μm

21 um

6



PSF WITH FRESNEL DIFFRACTION

L. Raimondi, D. Spiga, SPIE Proc., 8147 (2010)

- PSF computation from surface metrology
- At any energy
- Approximations:
 - Work in scalar approximation
 - Computation using the meridional profiles (1Dimension)





PSF WITH FRESNEL DIFFRACTION

L. Raimondi, D. Spiga, SPIE Proc., 8147 (2010)

ELECTRIC FIELD ON THE FOCAL PLANE OBTAINED BY THE CONSTRUCTIVE INTERFERENCE BETWEEN THE SPHERICAL WAVES GENERATED IN EACH POINTS OF THE MIRROR.

Kirchoff-Fresnel diffraction equation

$$U(P) = \frac{Ae^{ikr_0}}{r_0} \int \int_S \frac{e^{iks'}}{s'} K(\chi) dS'$$

$$PSF(x) = \frac{\Delta R}{f\lambda L^2} \left| \sum e^{-i\frac{2\pi}{\lambda}(\sqrt{(x-x_{\rm p})^2 + z_{\rm p}^2} - z_{\rm p})} \Delta \right|^2$$

In order to prevent mirror under sampling:

$$\Delta l \approx \frac{\lambda f^2}{2\pi R_0 r}$$
$$\Delta x \approx \frac{\lambda f^2}{\pi R_0 L}$$



PSF WITH FRESNEL DIFFRACTION

L. Raimondi, D. Spiga, SPIE Proc., 8147 (2011)

Two or more reflections

Double reflection



Focal spot computation with Fresnel diffraction: FEL case



$$u(x,z) = \frac{\omega_0}{\omega} e^{\left[-j(kz-\Phi) - x^2\left(\frac{1}{\omega^2} + \frac{jk}{2R}\right)\right]}$$

R(z) = wavefront curvature radius $k = 2\pi / \lambda \quad \Phi = \arctan(\lambda z / \pi \omega_0^2)$

$$E_{\rm h}(x_{\rm h}, z_{\rm h}) = \frac{1}{L\sqrt{\lambda x_{\rm h}}} \int_{\rm f}^{\rm d} (x, z_{\rm h}) = \frac{1}{L\sqrt{\lambda x_{\rm h}}} \int_{\rm f}^{\rm d} (x, z_{\rm h}) \frac{1}{d_2} e^{-\lambda (x_{\rm h}, z_{\rm h})} dz_{\rm p}$$

$$PSF(x) = \frac{\Delta R}{E_0^2 f \lambda L^2} \left| \sum_{k=1}^{\infty} E_k(x_k, z_k) e^{-i\frac{2\pi}{\lambda}(\sqrt{(x - x_k)^2 + z_k^2})} \Delta \right|^2$$

Focal spot simulations - DiProl

Focal spot K-B Vertical mirror at 32 nm



32 nm wavelenght

 K-B vertical best focus -2 mm from nominal FWHM_{32nm} = 5.8 μm

K-B horizontal best focus 0 mm from nominal FWHM_{32nm} = $4.4 \mu m$

Suggestion - the system limit in terms of the spot size should be lower than shadow predictions11

Focal spot measurements at DiProl end-station

Wave-front sensor measurements



FEL 1

- wavelength 32 nm
- measuring of Intensity and Wave-front at 1m out of nominal focus
- reconstruction of the spot in focal plane







- wavelength 32 nm
- diffraction limit spot-size at 32 nm FWHM = $4x5 \mu m$
- Best spot-size measured FWHM = $5x8 \mu m$

- Spot-size simulated with ray-tracing $FWHM = 10.5x18 \ \mu m$
 - Spot-size simulated with Fresnel diffraction at the common best focus (-1mm from the nominal focus) FWHM = $5.2x7.7 \mu m$

FUTURE WORK

- Characterization of the FEL wavefront by measuring the electric field with the wavefront sensor before K-B optics
- Put the measured electric field in the simulator evaluation of the performances of the optics (degradation/improvement of the wavefront)
- Implementation of the K-B system: new anti-twisting mounting - piezo-electric actuators for mirror shape correction

CONCLUSIONS

- We performed surface profile characterization of the K-B bendable system mounted in the DiProl chamber with Long Trace Profilometer.
- We extended the Fresnel diffraction method to FEL applications non isotropic sources - focal spot given the best measured profile at LTP - FWHM = 4.4x7.7 µm
- We provided several measurement campaigns of K-B system focalization in the DiProi end-station, 40x42 µm on the P-screen 15x26 µm on PMMA
- Through a wave-front sensor we went further in the optimization of the mirror shape.
 Focal spot (reconstructed via software) FWHM = 5x8 µm
- From the comparison between simulations and measures we conclude that the focal spot in a FEL can now be predicted by using the Fresnel diffraction method.

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